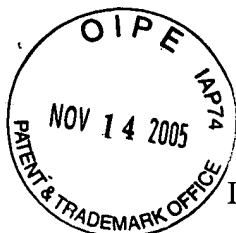


IFW



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Applicant:

Grant M. Kloster et al.

Serial No.: 10/782,329

Filed: February 19, 2004

For: Forming A Porous
Dielectric Layer

§
§
§
§
§
§
§
§

Art Unit: 2822

Examiner: Ida M. Soward

Docket: ITL.0946C1US
P15970C

Assignee: Intel Corporation

Mail Stop **Amendment**
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

REPLY TO OFFICE ACTION

Sir:

In response to the office action mailed August 24, 2005, please amend the above-referenced patent application as follows:

Date of Deposit: November 9, 2005
I hereby certify under 37 CFR 1.8(a) that this correspondence is being deposited with the United States Postal Service as **first class mail** with sufficient postage on the date indicated above and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.
Cynthia L. Hayden
Cynthia L. Hayden